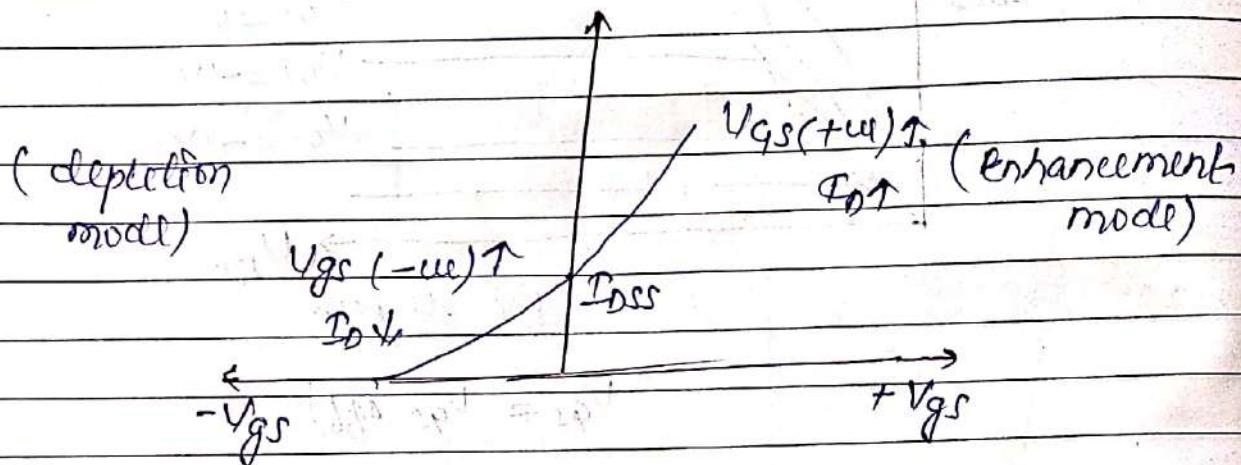


cut-off region \therefore At $V_{GS} = V_{GS\text{ off}}$, $I_D = 0$
and curve lies on horizontal axis.

Transfer curve for N-CH MOSFET \therefore

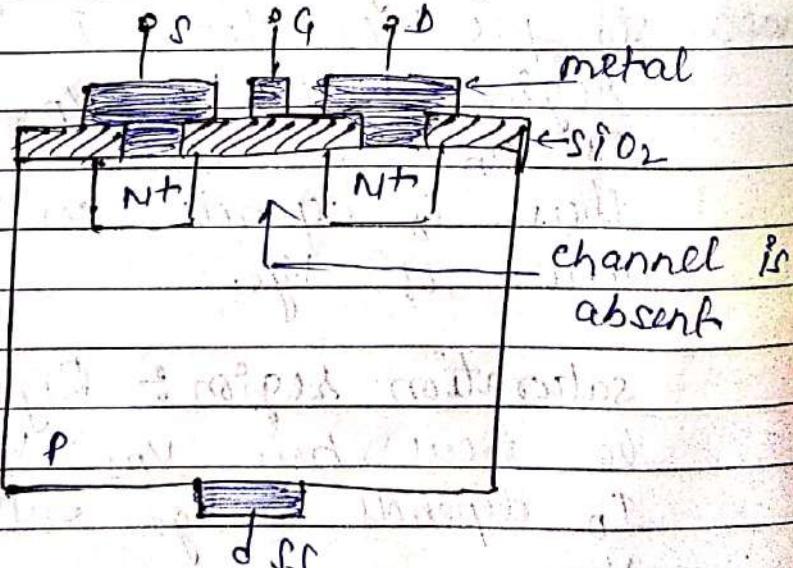


gives a plot b/w I_D and V_{GS} for constant V_{DS} . In enhancement mode I_D increases and in depletion layer mode I_D decreases.

Enhancement mosfet \therefore It is of two types -

- P-CH MOSFET and • N-CH MOSFET.

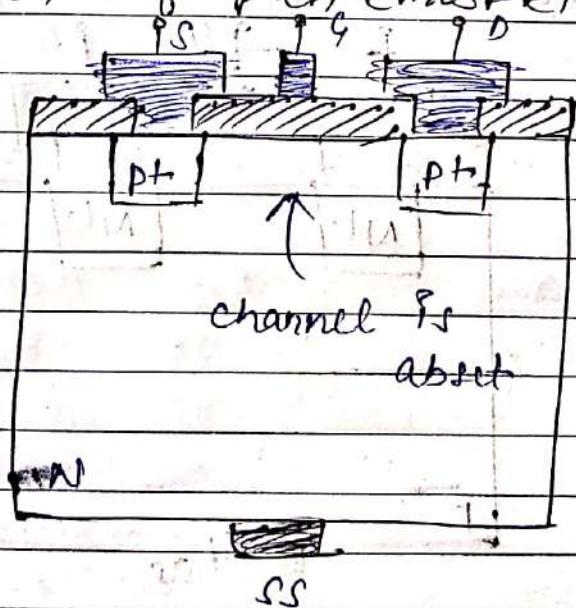
Construction of N-CH MOSFET \therefore



- A slab of p-type semi-conductor is used as substrate.
- The drain and source terminals are connected at doped region through metal contact.
- Channel is physically absent.
- SiO_2 layer is present which isolates gate terminal from the substrate.

The construction is very similar to that of depletion type MOSFET the only diff is that channel is absent.

construction of p-ch EMOSFET



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no interest among Van Zandt, all inferior demand from the international market.

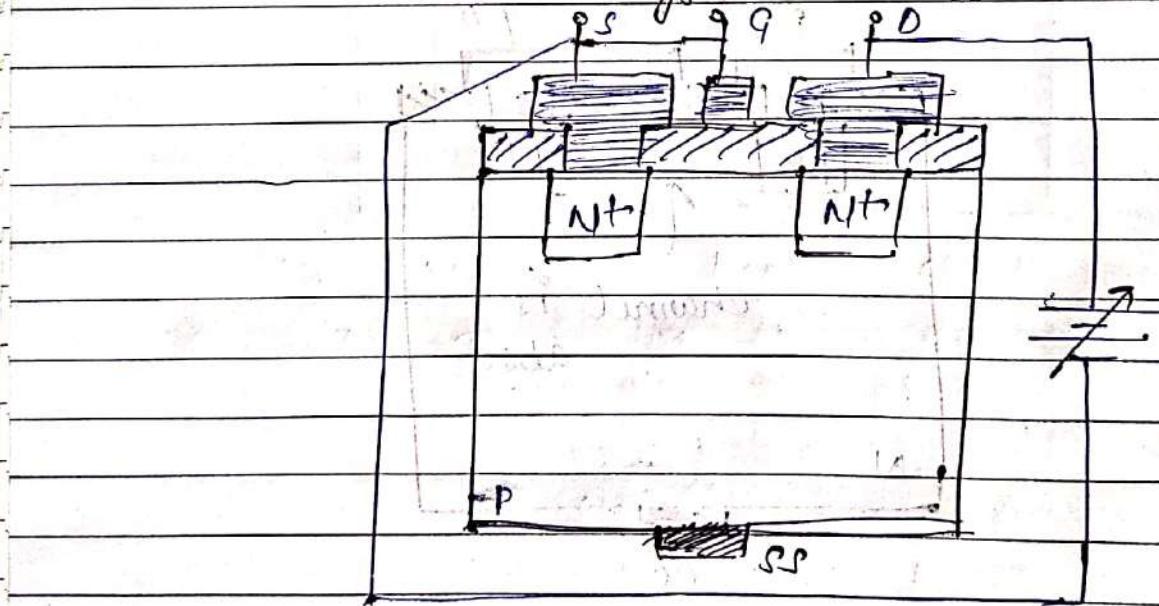
plano: affinità e si modo

3500-35000 ft. - Minas Gerais Brazil 1961-1972
- *Theridion* sp. with *Theridion*

100% of the time have worked

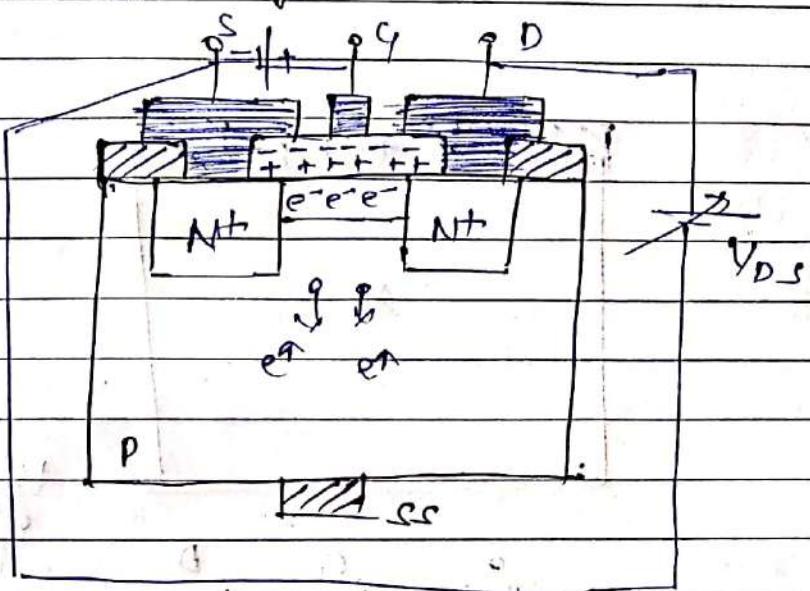
working of N-CH EMOS DCT +

case 1 :- when $V_{GS} = 0$, and V_{DS} is applied.



at $V_{GS} = 0$ and a two charge voltage is applied b/w drain and source then due to absence of n-type channel, $I_D = 0$

case 2: when $V_{GS} > 0$ (true value)

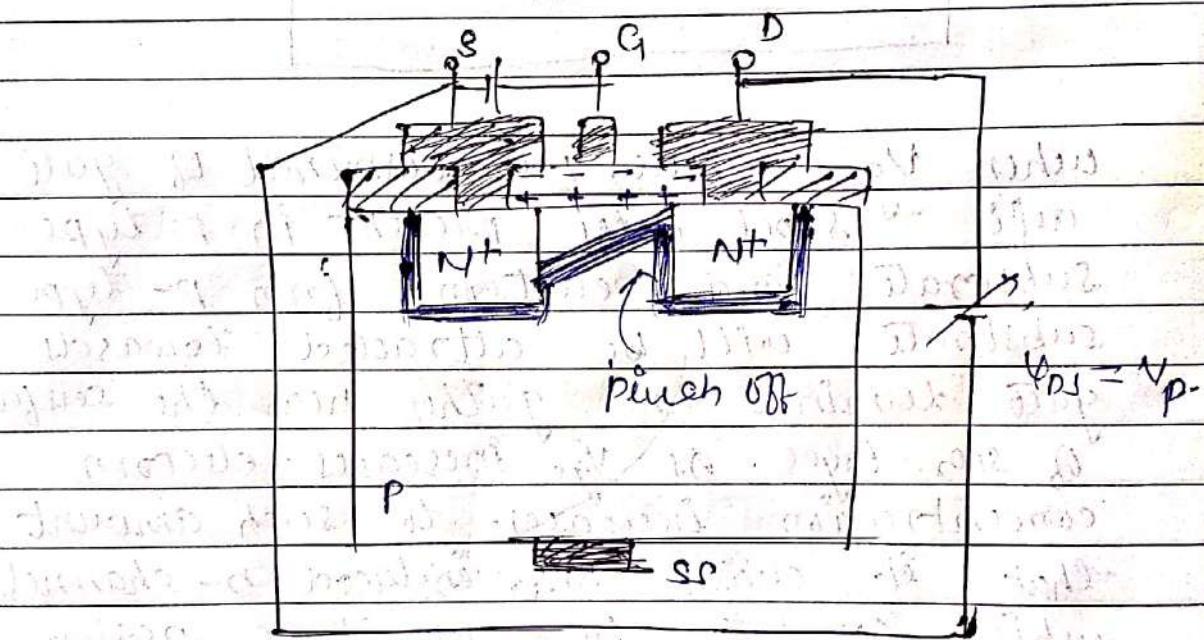
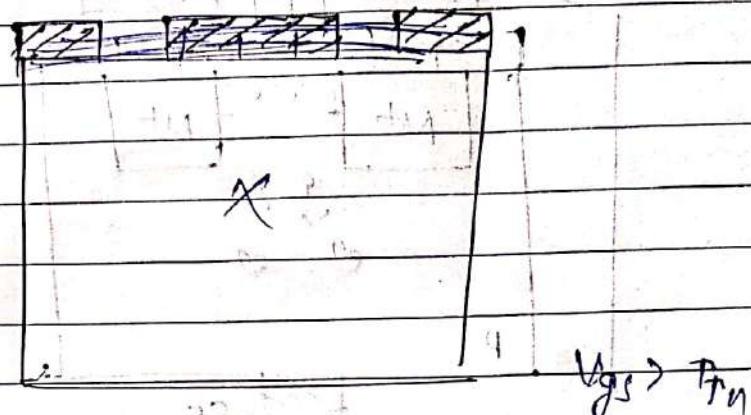


when V_{GS} is true, the terminal of gate will repel holes present in P-type substrate and electrons from P-type substrate will be attracted towards gate terminal and gather near the surface of SiO_2 layer. as V_{GS} increases electron concentration increases to such amount that it creates an induced n-channel which connects both n+ type region now drain current starts flowing through the induced channel.

The minimum value of V_{GS} at which channel conduction begins is called threshold voltage, V_{TH} .

case 3: Effect of Var.

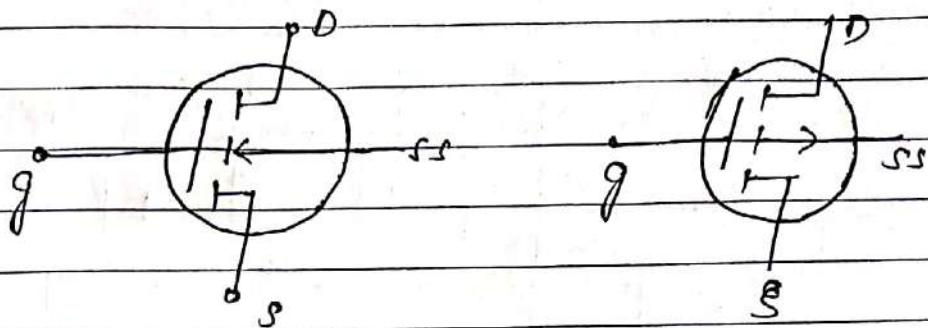
P.T.O.



If $V_{GS} \geq V_{TH}$ and kept constant and V_{DS} increases gradually the induced channel becomes narrow at drain end.

If V_{DS} increases the channel width will be reduced to a point of pinch off. and a saturation condition will be established. In this case current I_D becomes constant and independent of V_{DS} .

Circuit symbols :-



N-CH MOSFET

P-CH MOSFET

O/P characteristic curve for N-CH MOSFET :-

